



Product Information Sheet

Ufaryl DL - 90C

Linear Alkyl Benzene Sulphonate, Sodium Salt

CAS #:	68411-30-3
Chemical Formula:	R-O-SO ₃ -Na Carbons in alkyl chain R=10-13 = SO ₃ Na ⁺
Appearance And Odor:	Ivory White Free Flowing Flake
Molecular Weight:	344

Application:

UFARYL DL 90 C is an anionic surfactant based on linear alkyl benzene sulphonate (C 10-13). The product is free flowing powder with excellent detergency and wetting properties. UFARYL DL 90 C is customized to meet performance needs for toilet block/care applications. UFARYL DL 90 C is a high active powder material containing functional additives and anti lime scale agent for enhanced processing and increased detergency performance. UFARYL DL 90 C is the main active ingredient in toilet blocks. The product is easily biodegradable.

Chemical Analysis:

Component	Typical	Guaranteed
Active Content (W/W%)	89.9	Min 88 - Max 92
Water	1.6	Min 0 - Max 2.0
Inorganic Salts	Balance	

Physical Properties:

Component	Typical	Guaranteed
pH: (1% Solution):	7.6%	7.0 - 9.0%
Bulk Density (g/l)	420	370 - 470

Packaging:

UFARYL DL 90C is shipped in 25 kg/18 bags on shrink-wrapped pallets. It has a strong hygroscopic character, and will absorb humidity if exposed to open air. Store at room temperature and dry.

GHS Labeling Information:



Signal Word
Danger

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